Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	137231	"CVD" and (heat\$4 or thermal\$4) and chamber and temperature and (supply or feed) and hexaethylaminodisilane and ammonia and gas "silicon nitride"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/09 12:46
S2	0	"CVD" and (heat\$4 or thermal\$4) and chamber and temperature and (supply or feed) and hexaethylaminodisilane and ammonia and gas and "silicon nitride"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/09 12:47
S3	0	(heat\$4 or thermal\$4) and chamber and temperature and (supply or feed) and hexaethylaminodisilane and ammonia and gas and "silicon nitride"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/09 12:47
S4	3	"hexaethylaminodisilane"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/09 12:47
S5	1	"hexaethylaminodisilane" and heat and substrate and chamber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 09:22
S6	. 6	"6475902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 09:23